## IN THE CLAIMS

The status of the claims is reproduced below.

1. (Currently Amended): A method for cleaning a resist residue on a microstructure comprising fluidizing a cleaning agent composition consisting essentially of carbon dioxide and a cleaning component under a pressure of 5 Mpa or more, and bringing the cleaning agent composition into contact with a resist residue on a microstructure, wherein hydrogen fluoride is used as the cleaning component, wherein the hydrogen fluoride concentration in the cleaning agent composition is 0.0001 to 0.05% by mass.

Claim 2: (Canceled).

- 3. (Original): The method according to Claim 1, wherein the cleaning agent composition is prepared by mixing hydrofluoric acid and high-pressure carbon dioxide.
- 4. (Original): The method according to Claim 3, wherein the water content in the cleaning agent composition is controlled to 0.0001 to 0.5% by mass.

Claim 5: (Canceled).

- 6. (Original): A microstructure cleaned by the method according to Claim 1.
- 7. (Currently Amended): A method for cleaning a resist residue on a microstructure comprising:

fluidizing a cleaning agent composition consisting essentially of carbon dioxide, a cleaning component and 1% by mass or more of an alcohol under a pressure of 5 Mpa or more, and

bringing the cleaning agent composition into contact with <u>a resist residue on</u> a microstructure, wherein hydrogen fluoride is used as the cleaning component, wherein the hydrogen fluoride concentration in the cleaning agent composition is 0.0001 to 0.05% by mass.

- 8. (Previously Presented): The method according to Claim 7, wherein the cleaning agent composition is prepared by mixing hydrofluoric acid and high-pressure carbon dioxide.
- 9. (Previously Presented): The method according to Claim 7, wherein the water content in the cleaning agent composition is controlled to 0.0001 to 0.5% by mass.
- 10. (Previously Presented): A microstructure cleaned by the method according to Claim 7.

## SUPPORT FOR THE AMENDMENTS

The amendments to Claims 1 and 7 are supported by the specification and the original claims. Accordingly, no new matter is believed to have been added to the present application by the amendments submitted above.

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